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	Application No.	Applicant(s)	710
Notice of Allowability	10/747,830	KIM, DAE KYEUN	
	Examiner	Art Unit	
	Chuong A Luu	2825	
The MAILING DATE of this communication appearance All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate communication. This application is su	this application. If not include nication will be mailed in due	ed course. THIS
1. This communication is responsive to			
2. The allowed claim(s) is/are 1-12.			
3. \boxtimes The drawings filed on <u>29 December 2003</u> are accepted by	the Examiner.		
 4.	been received. been received in Application cuments have been received of this communication to file a dent of this application. itted. Note the attached EXAL is reason(s) why the oath or one of the submitted. son's Patent Drawing Review of Amendment / Comment or in the header according to 37 CFR is it of BIOLOGICAL MATE	in this national stage applicate reply complying with the red MINER'S AMENDMENT or Noteclaration is deficient. (PTO-948) attached the Office action of the drawings in the front (not the tal.121(d).	quirements OTICE OF
 Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 3/25/04 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material 	6. ☐ Interview Sur Paper No./N 7. ☐ Examiner's A	Mail Date Amendment/Comment Statement of Reasons for Allo	·

DETAILED ACTION

Allowable Subject Matter

Claims 1-12 are allowed.

The following is an examiner's statement of reasons for allowance: The examiner has reviewed the prior art in light of applicant's claimed invention and finds that the combined claims define over the prior art. The cited prior art does not disclose or suggest a process to form a semiconductor device inter alia the limitations "....forming an interlayer dielectric (ILD) pattern with contact holes over the substrate including the gate electrode and the first preliminary source/drain region, the contact holes exposing the top of the gate electrode and some part of the first preliminary source/drain region; forming an expanded source/drain region by performing an ion implantation using the ILD pattern as a mask, the expanded source/drain region including the first preliminary source/drain region with shallow junction as the LDD region and a second preliminary source/drain region with deep junction....".

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Conclusion

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chuong A Luu whose telephone number is (571) 272-1902. The examiner can normally be reached on M-F (6:30-3:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on (571) 272-1907. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

CAL September 3, 2004

MATTHEW SMITH SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800